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OAI WINS ORDER FOR NANO IMPRINT from TRINITY COLLEGE

May 27, 2008, San Jose, CA: **OAI**, a manufacturer of UV exposure equipment for Semiconductor, Microfluidics, and Nano Technology, announces it has won the bid from Trinity College, Ireland for a Nano Imprint Module on OAI's Model 800 Optical Backside Mask Aligner. This Nano Imprint Technology was developed at HP Labs. Trinity College purchased the Nano Imprint Module for both its R & D and teaching facilities. OAI's Nano Imprint Module will be integrated with OAI's Model 800 front and backside aligner.

"We are pleased to work with Trinity College to help them include Nano Technology in their research and teaching programs," said Dr. Charles Turk, President of OAI. "The use of the imprint module with the Model 800 Mask Aligner provides a flexible platform for advanced semiconductor lithography, MEM's, as well as Nano Imprinting. The change over from lithography to nano imprinting can be accomplished in less than 15 minutes," he added. The system is scheduled for installation this summer. OAI's Nano Imprint Module can be added to any mask aligner.

OAI is a leading manufacturer of precision equipment used in the Semiconductor, MEMS, and Compound Semiconductor Industries for over 30 years. Located in Silicon Valley, **OAI** can be contacted via e. mail: [sales @oainet.com](mailto:sales@oainet.com),
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